

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): SHIMAZU et al

Serial No.:

Filed: January 22, 2004

For: Semiconductor Device And Its Production Process

REAFFIRMATION OF CLAIM FOR PRIORITY

Mail Stop: Application
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

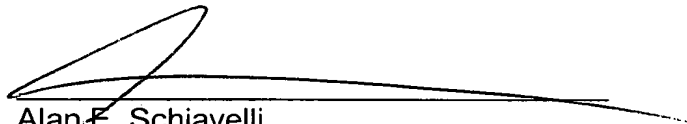
January 22, 2004

Sir:

Under the provisions of 35 USC §119 and 37 CFR §1.55, Applicants hereby claim the right of priority based on Japanese Patent Application No. Japanese Application No. 10-267695, filed in Japan on September 22, 1998.

The certified copy of the above-referred to Japanese Patent Application was received by the International Bureau in prior application Serial No. 09/787,743, filed June 8, 2001.

Respectfully submitted,



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FORM PTO-1449 U.S. Department of Commerce
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APPLICANT

SHIMAZU et al

FILING DATE

January 22, 2004

GROUP

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
			2	8	6	0	6	2	1/91	Germany				
		9	1	3	9	4	7	5	5/97	Japan				
		3	2	4	8	5	6	2	11/91	Japan				
			6	2	9	2	8	8	2/94	Japan				
		60	2	1	3	0	5	8	10/85	Japan				
		3	1	6	6	7	3	5	7/91	Japan				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Mo et al "Formation and Properties of Ternary Silicide (CoNi)Si ₂ Thin Films, IEEE 1998 5th International Conference on Solid State And Integrated Circuit Technology pp 271-274
	Hong et al "Magneto-Optic Kerr Effect Measurements on FeCoSi Epitaxially Stabilized on Si (111), Journal of Magnetism and Magnetic Materials, vol. 165 pp 212-215
	http://www.puretechnic.com and http://tosohsmd.com/tsprod.tspcobdt.htm , Material Data Sheet MDS 27.000 which includes the total metallics of the cobalt target, pp 1-4 and 1-3

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation is considered, draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

